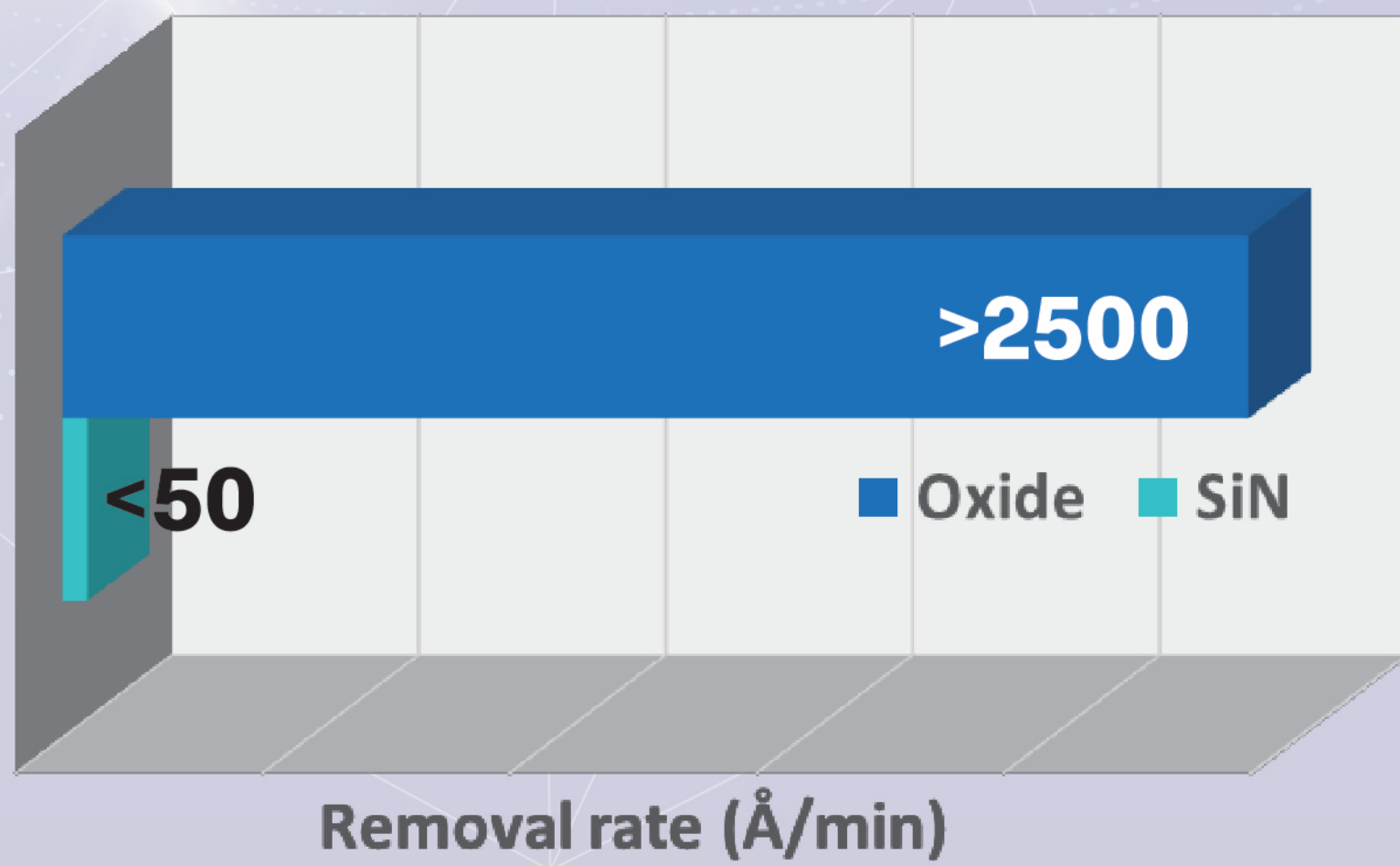


JSR CMP Slurry

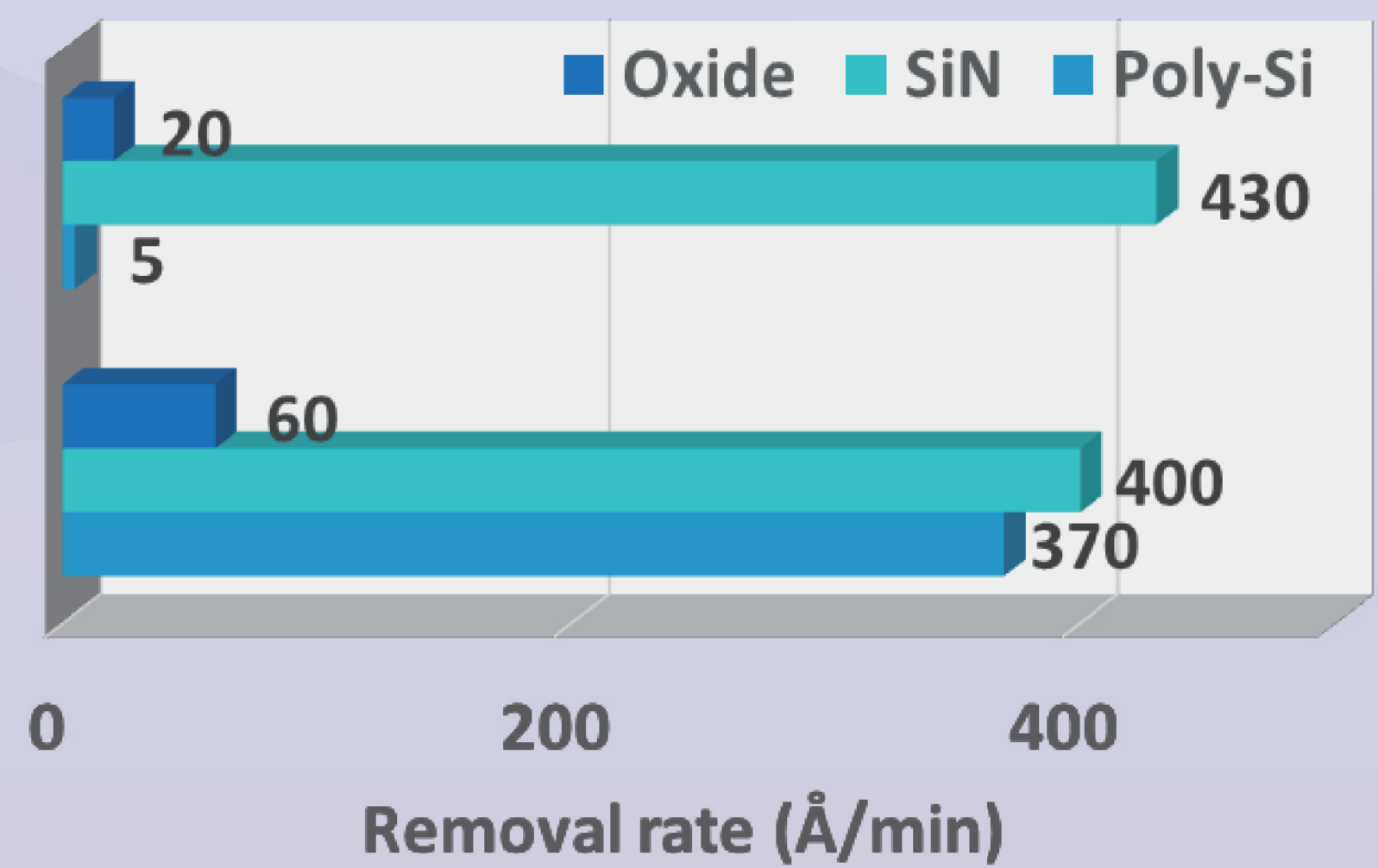
Oxide Slurry

High oxide RR with highly associated silica abrasive

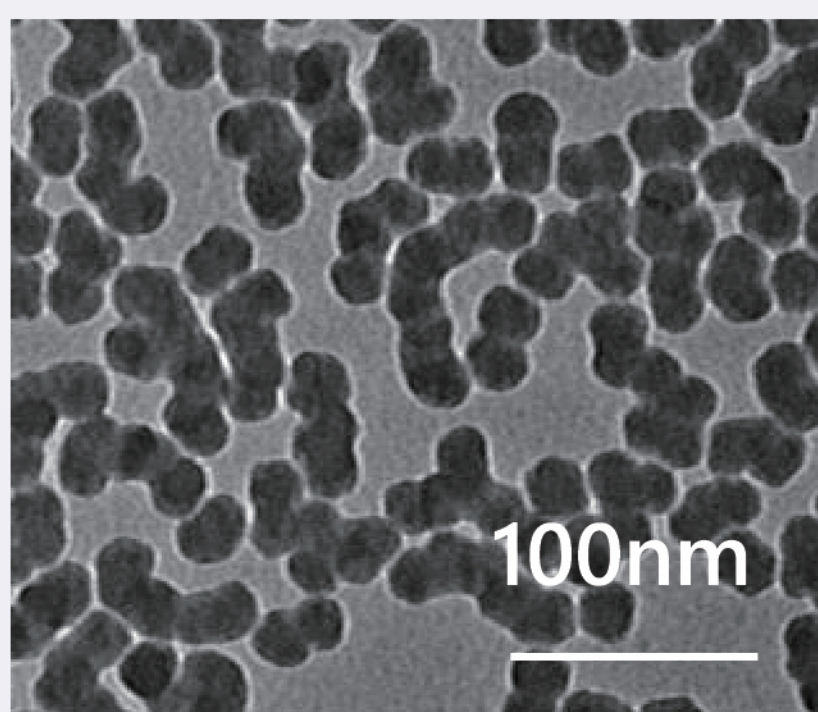


SiN Slurry

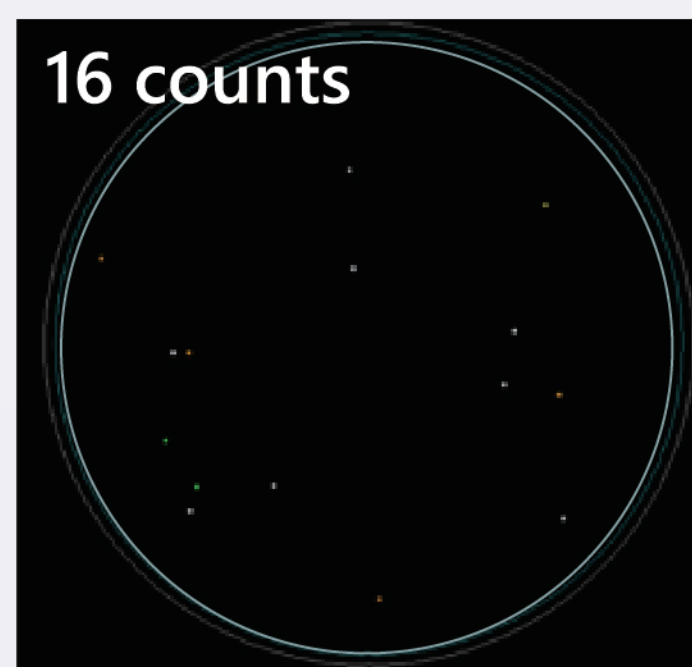
**High SiN RR by Zeta potential control
Tunable Poly-Si RR by additive selection**



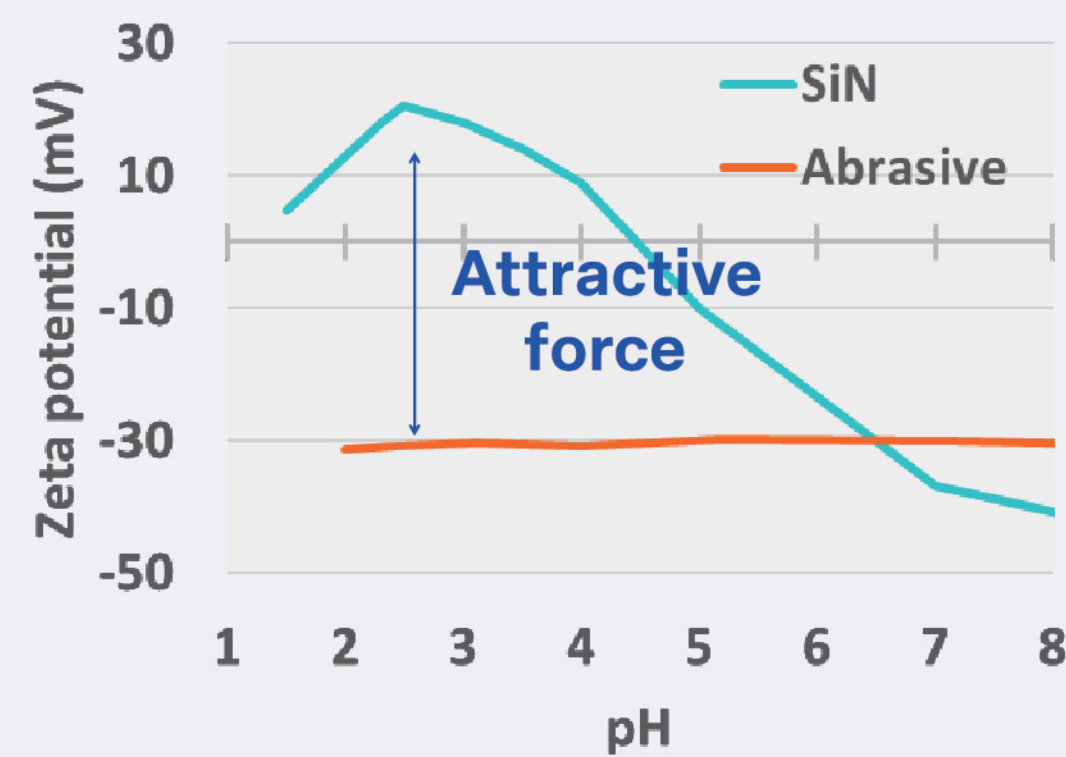
High degree of association abrasive



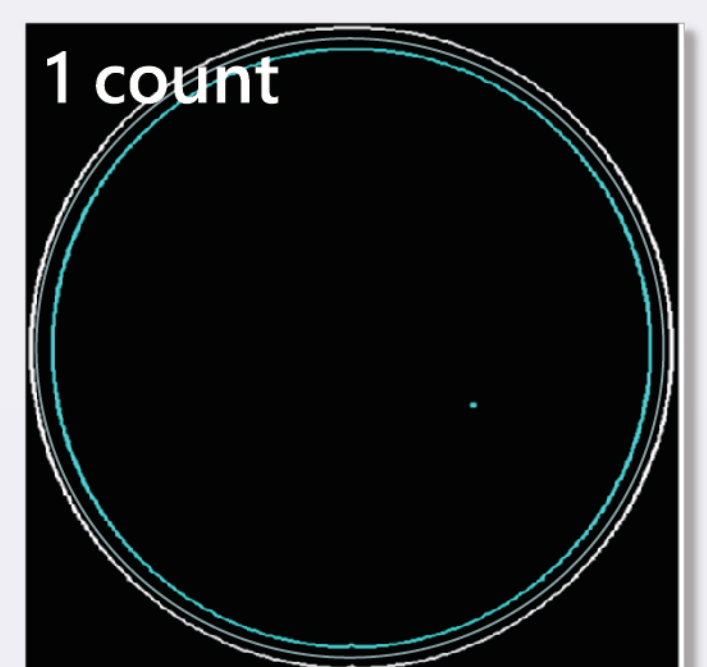
TEM Image



Defectivity (Oxide)



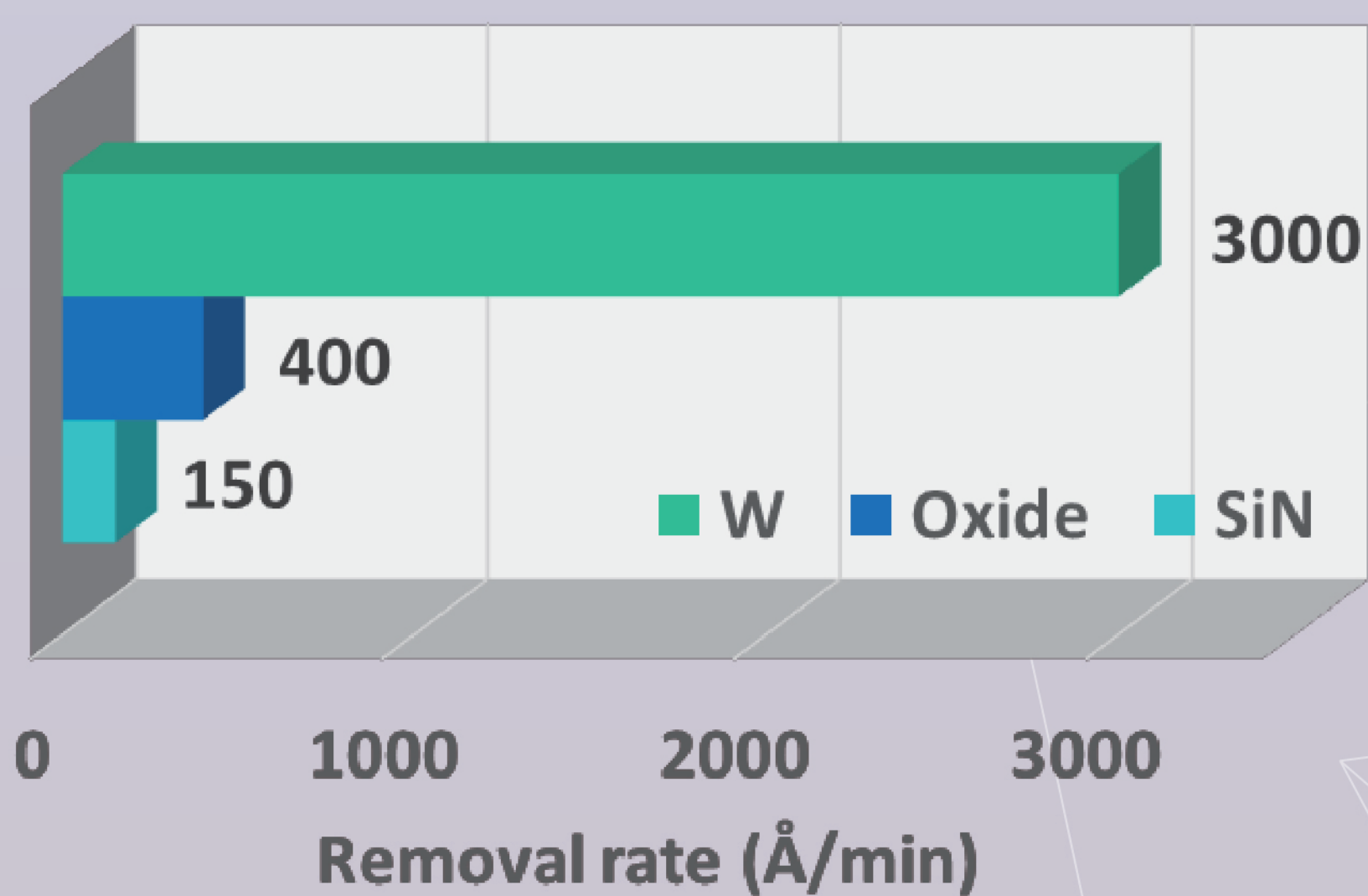
Zeta potential



Defectivity (SiN)

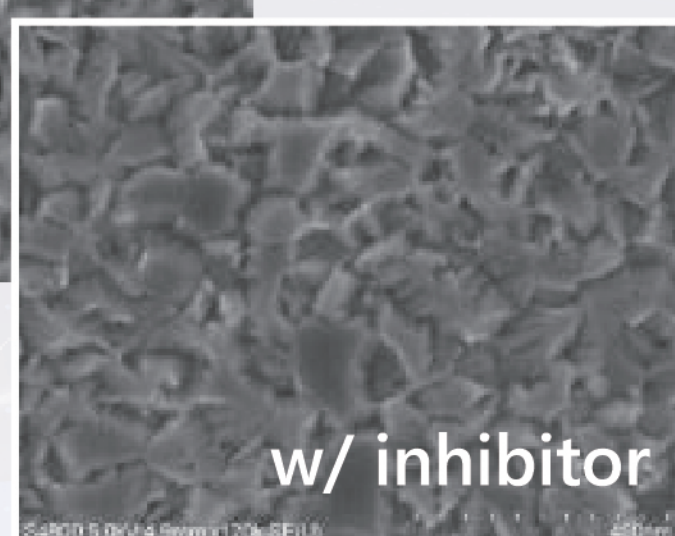
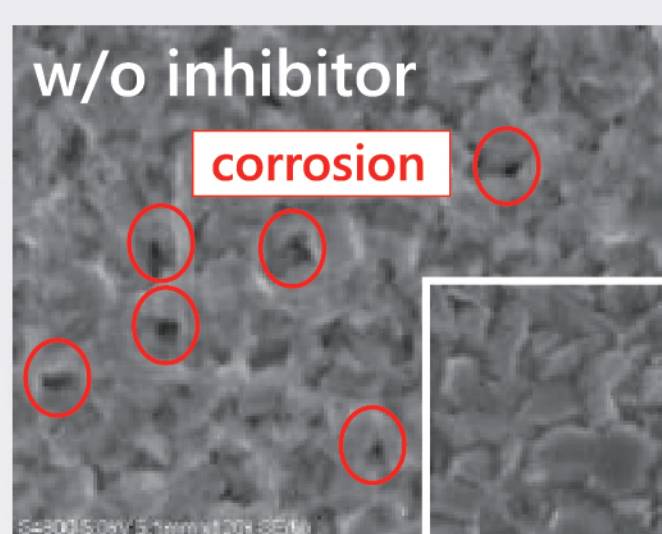
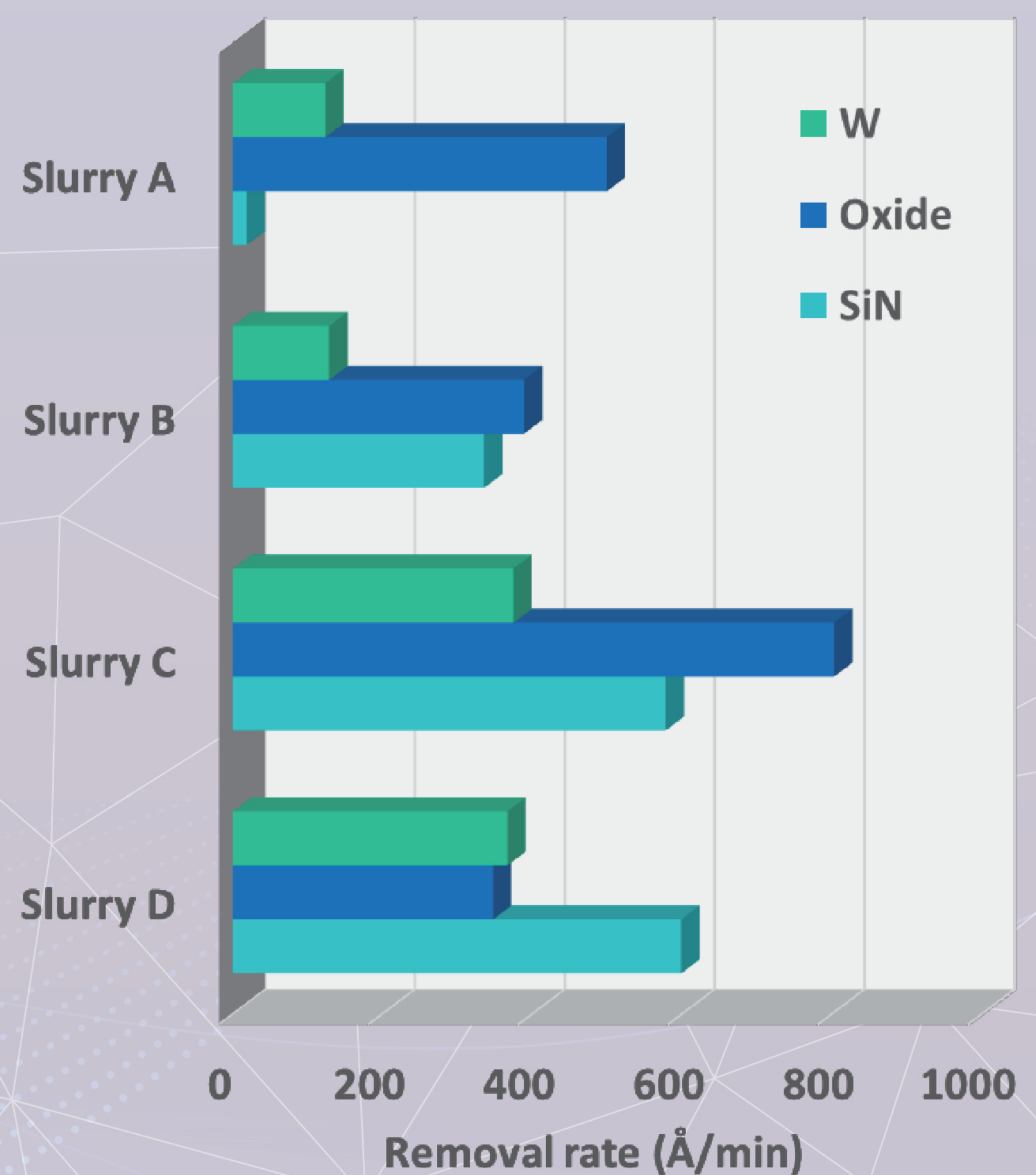
W Bulk Slurry

**High W RR by catalyst system
W corrosion free by JSR inhibitor**



W Buff Slurry

Tunable selectivity to create well-controlled surface



SEM Image (W surface)



Defectivity (W)